



Docket No.: 0171-1063P  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

---

In re Patent Application of:  
Youichi OHSAWA et al.

Application No.: 10/776,159

Confirmation No.: 3759

Filed: February 12, 2004

Art Unit: 1626

For: NOVEL SULFONYLDIAZOMETHANES,  
PHOTOACID GENERATORS, RESIST  
COMPOSITIONS, AND PATTERNING  
PROCESS

---

Examiner: F. Powers

**AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated November 21, 2005, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

**Amendments to the Specification** begin on page 2 of this paper.

**Remarks/Arguments** begin on page 3 of this paper.